

EUV Systems for High Volume Manufacturing

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ASML NXE:3400 and NXE:3600D scanners are firmly embedded in High Volume Manufacturing (HVM) of 7 nm to 3 nm logic devices as well as 10 nm class memory devices. In this presentation we will share the latest performance of these systems, including excellent overlay, reliability, and high productivity.

We will describe the latest technology supporting the ASML roadmap for further improving cost of technology via increased productivity and share system qualification and performance data of the next HVM scanner, the NXE:3800E. In addition we will share the latest status of the next generation of EUV systems, the 0.55 NA EXE:5000.

Lastly the ASML NXE sustainability roadmap showing progress and steps towards a significant reduction in energy consumption per wafer exposure on NXE systems will be presented.